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Total Number of Pages in This Submission

Application Number 10/694,284

Filing Date October 27, 2003

First Named Inventor Frank Y. Xu

Art Unit Unassigned

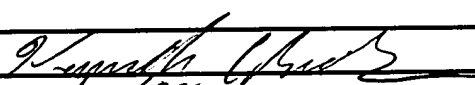
Examiner Name Unassigned

Attorney Docket Number PA94-36-03

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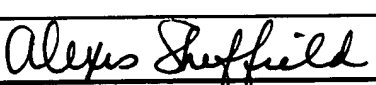
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Xu et al.

PATENT APPLICATION

Serial No.: 10/694,284

Group Art Unit: Unassigned

Filing Date: 10/27/2003

Examiner: Unassigned

For: METHODS FOR FABRICATING PATTERNED FEATURES UTILIZING  
IMPRINT LITHOGRAPHY.

INFORMATION DISCLOSURE STATEMENT

Commissioner  
for Patents  
Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and the requisite copies of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
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#### OTHER PATENT DOCUMENTS

<u>Application Number</u>	<u>Inventor</u>	<u>Filing Date</u>
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10/264,926	Sreenivasan et al.	10/04/2002
10/396,615	Sreenivasan et al.	03/25/2003
10/423,642	Sreenivasan et al.	04/25/2003
10/463,396	Choi et al.	06/17/2003

#### PATENT APPLICATION PUBLICATIONS

<u>Publication Number</u>	<u>Inventor</u>	<u>Publication Date</u>
US 2002/0098426	Sreenivasan et al.	07/25/2002
US 2002/0094496	Choi et al.	07/18/2002
US 2003/0093122	Choi et al.	07/18/2002
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<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
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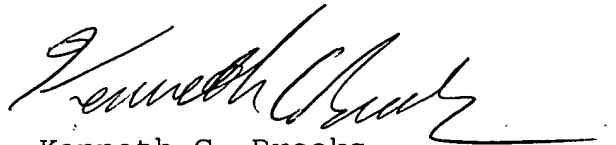
Bender M. et al., "Fabrication of Nanostructures Using A UV-based Imprint Technique," *Microelectronic Engineering*, pp. 223-236, 2000

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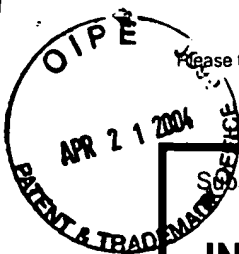


Kenneth C. Brooks  
Reg. No. 38,393

P.O. Box 81536  
Austin, Texas 78708-1536  
Telephone: 512-527-0104  
Facsimile: 512-527-0107  
patentsrus@earthlink.net



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Sheet 3 of 5

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Application Number	10/694,284
Filing Date	10/27/2003
First Named Inventor	Xu et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	PA94-36-03

**OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	A22	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A23	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A24	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A25	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
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	A27	XIA et al., "Soft Lithography," Annu. Rev. Mater. Sci., 1998, pp. 153-184, vol. 28.	
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	A29	WU et al., "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3825-3829, vol. B 16(6).	
	A30	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
	A31	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	A32	RUCHHOEFT et al., "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, pp. 2965-2982, vol. 17.	

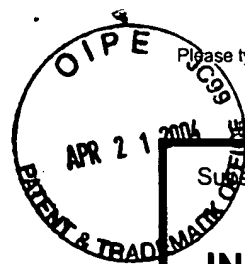
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First Named Inventor	Xu et al.
Group Art Unit	Unassigned
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Attorney Docket Number	PA94-36-03

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	A33 /	CHOU, "Nanoimprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	
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Group Art Unit	Unassigned
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	A44	WATTS et al., "Method For Fabricating Bulbous-Shaped Vias," U.S. Patent Application Publication 2004/0038552. Published on February 26, 2004.	
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